

L Number	Hits	Search Text	DB	Time stamp
1	16613	(etch\$3 remov\$3) near3 oxide same metal	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 12:13
2	696	((etch\$3 remov\$3) near3 oxide same metal) and polish\$3 near3 metal	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 09:01
3	0	((etch\$3 remov\$3) near3 oxide same metal) and polish\$3 near3 metal) and \$5flourocarbon	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 09:02
4	0	((etch\$3 remov\$3) near3 oxide same metal) and polish\$3 near3 metal) and \$5flourocarbon\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 09:02
5	0	((etch\$3 remov\$3) near3 oxide same metal) and polish\$3 near3 metal) and flourocarbon\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 09:02
6	27	((etch\$3 remov\$3) near3 oxide same metal) and polish\$3 near3 metal) and \$5fluorocarbon\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 10:18
7	5295	(etch\$3 remov\$3) near5 metal near oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 10:18
8	150	((etch\$3 remov\$3) near5 metal near oxide) and \$5fluorocarbon\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 11:50
9	1	etch\$3 near5 metal near oxide same ph same (potassium near hydroxide koh)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 11:51
10	6	etch\$3 near5 metal near oxide same ph and (potassium near hydroxide koh)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 11:55
11	94464	etch\$3 near5 metal near oxide an ph and (potassium near hydroxide koh)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 11:55
12	27	etch\$3 near5 metal near oxide and ph and (potassium near hydroxide koh)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 11:55
13	21	(etch\$3 near5 metal near oxide and ph and (potassium near hydroxide koh)) not (etch\$3 near5 metal near oxide same ph and (potassium near hydroxide koh))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 12:02
14	317	438/754.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 12:03
15	18	438/754.ccls. and ph and etch\$3 near3 oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 12:10
16	6	etch\$3 near (cuo copper near oxide tungsten near oxide) same ph	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 12:10
17	66	etch\$3 near3 oxide same metal same ph	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 12:13

-	9162	polish\$3 near4 metal and (cu copper w tungsten al aluminum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 09:00
-	1400	(polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/10 07:51
-	1177	((polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide) and semiconductor	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/10 07:51
-	984	((polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide) and semiconductor) and chemical near mechanical	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/10 07:52
-	68	((polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide) and semiconductor) and chemical near mechanical) and (fluorocarbon\$1 hydrofluorocarbon\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/10 07:53
-	186	((polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide) and semiconductor) and chemical near mechanical) and (potassium near hydroxide koh)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/15 12:56
-	1	("5,527,423").PN.	USPAT	2003/07/10 09:56
-	9	("5478436"   "5482174"   "5645737"   "5830280"   "5972862"   "6043206"   "6090214"   "6162301"   "6171405").PN.	USPAT	2003/07/10 09:25
-	22	("4370173"   "4376673"   "4871422"   "5200024"   "5286300"   "5354712"   "5382296"   "5630904"   "5662769"   "5700383"   "5705089"   "5714203"   "5794299"   "5806126"   "5810938"   "5824601"   "5895563"   "5897375"   "5954997"   "5965036"   "5972862"   "5981454").PN.	USPAT	2003/07/10 09:27
-	14	("4879258"   "4960485"   "5196353"   "5314843"   "5514245"   "5730642"   "5775980"   "5837557"   "5859466"   "5934980"   "5957750"   "6020262"   "6120347"   "6150271").PN.	USPAT	2003/07/10 09:41
-	2745	438/691-693,695,722,723,724.ccls.	USPAT	2003/07/10 09:57
-	209	((polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide) and 438/691-693,695,722,723,724.ccls.	USPAT	2003/07/10 09:57
-	145	((polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide) and 438/691-693,695,722,723,724.ccls. ) not (((polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide) and semiconductor) and chemical near mechanical) and (potassium near hydroxide koh)	USPAT	2003/07/10 09:58
-	13	((("6383934") or ("5934980") or ("6162301") or ("6265781") or ("5981454") or ("6546939") or ("6432825") or ("6464568") or ("5482174") or ("6171405") or ("5954997") or ("5934980") or ("5806126") or ("5830280")).PN.	USPAT	2003/09/15 12:57